

Title (en)  
Method for manufacturing tiles having their exposed side provided with depressions and reliefs to reproduce the appearance of split quarrrystone

Title (de)  
Verfahren zur Herstellung von Fliesen mit Vertiefungen und Reliefs auf der freiliegenden Seite um das Erscheinungsbild von Bruchstein nach zu bilden

Title (fr)  
Procédé de fabrication de carreaux avec face visible pourvue de dépressions et de reliefs pour simuler l'apparence de pierre de carrière fondue

Publication  
**EP 1101584 A3 20030326 (EN)**

Application  
**EP 00203852 A 20001103**

Priority  
IT RE990116 A 19991115

Abstract (en)  
[origin: EP1101584A2] The method comprises the following operations: in a usual mould, forming a crude tile from an atomized powder mix, that mould punch intended to create the exposed face of the tile reproducing the appearance of split quarrrystone or of a non-flat surface; drying the thus formed tile in a continuous dryer in accordance with a usual drying cycle; applying on the exposed side of the dried tile at least one layer of coloured atomized clay or of pigment in powder form, to at least partly cover said side of the tile; subjecting the exposed side of the tile to the action of an air stream at an incidence angle tending towards zero; kiln-firing the tile treated in this manner in accordance with a usual firing cycle. <IMAGE>

IPC 1-7  
**B28B 3/02**; **B28B 11/04**; **B28B 7/00**; **B28B 11/00**

IPC 8 full level  
**B28B 3/00** (2006.01); **B28B 7/00** (2006.01); **B28B 7/34** (2006.01); **B28B 11/04** (2006.01); **B28B 11/08** (2006.01); **E04F 13/14** (2006.01)

CPC (source: EP)  
**B28B 3/003** (2013.01); **B28B 7/0064** (2013.01); **B28B 7/342** (2013.01); **B28B 11/044** (2013.01); **B28B 11/08** (2013.01); **B28B 11/0872** (2013.01); **E04F 13/147** (2013.01)

Citation (search report)  
• [E] PATENT ABSTRACTS OF JAPAN vol. 2000, no. 26 1 July 2002 (2002-07-01)  
• [AX] PATENT ABSTRACTS OF JAPAN vol. 018, no. 236 (C - 1196) 6 May 1994 (1994-05-06) & DATABASE WPI Week 199409, Derwent World Patents Index; AN 1994-071765, XP002223309  
• [AX] PATENT ABSTRACTS OF JAPAN vol. 1995, no. 09 31 October 1995 (1995-10-31)  
• [AX] PATENT ABSTRACTS OF JAPAN vol. 017, no. 164 (M - 1390) 30 March 1993 (1993-03-30)  
• [A] PATENT ABSTRACTS OF JAPAN vol. 1995, no. 11 26 December 1995 (1995-12-26)

Cited by  
EP1707331A3; WO2009092977A2; WO2009092977A3

Designated contracting state (EPC)  
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE TR

DOCDB simple family (publication)  
**EP 1101584 A2 20010523**; **EP 1101584 A3 20030326**; IT 1311048 B1 20020228; IT RE990116 A0 19991115; IT RE990116 A1 20010515

DOCDB simple family (application)  
**EP 00203852 A 20001103**; IT RE990116 A 19991115